

Title (en)

A METHOD FOR PRODUCING A CHANNEL REGION LAYER IN A VOLTAGE CONTROLLED SEMICONDUCTOR DEVICE

Title (de)

VERFAHREN ZUR BILDUNG EINES KANALGEBIETS IN EINER SIC-SCHICHT FÜR EIN SPANNUNGSGESTEUERTES HALBLEITERBAUELEMENT

Title (fr)

PROCEDE DE PRODUCTION D'UNE COUCHE D'UNE REGION CANAL DANS UN DISPOSITIF A SEMI-CONDUCTEUR COMMANDE PAR TENSION

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Application

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IPC 8 full level

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